

Figure 1: Temperature dependence of the ALD process using methanol and RuO_4 as reactants, showing the growth per cycle as a function of substrate temperature, as obtained from XRR.

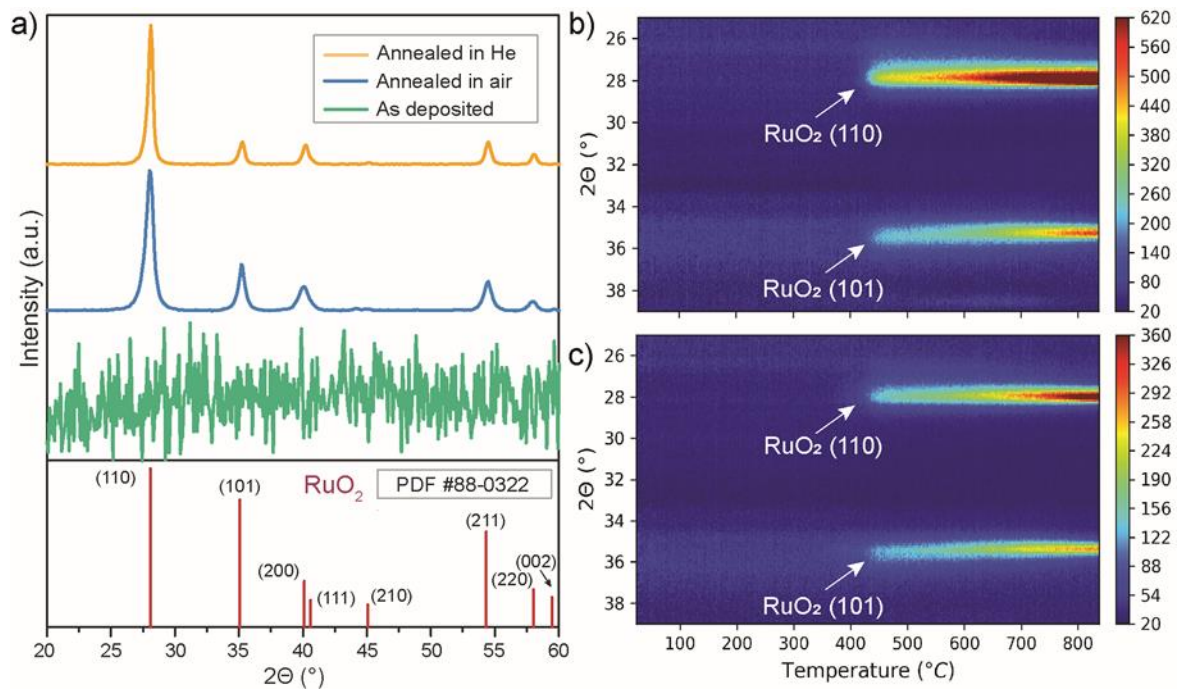


Figure 2: **a)** *Ex situ* X-ray diffractograms of the as-deposited, He-annealed, and air-annealed RuO_2 films. **b)** and **c)** *In situ* XRD patterns acquired during the anneals in helium and air, respectively.

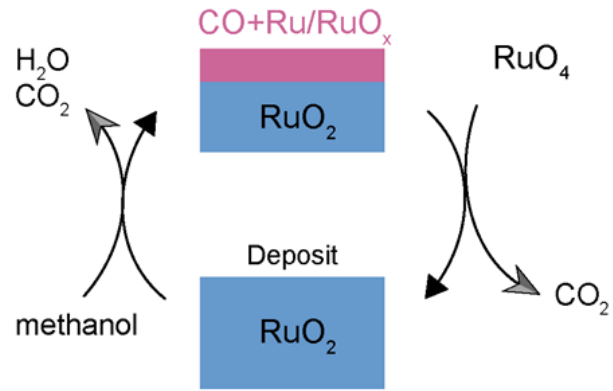


Figure 3: Reaction mechanism of the developed RuO₂ ALD process.